



Docket No.: 50432-485

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	:	Customer Number: 20277
Wen-Jie QI, et al.	:	Confirmation Number: 2309
Serial No.: 10/023,328	:	Group Art Unit: 1765
Filed: December 20, 2001	:	Allowed: April 21, 2004
	:	Examiner: Lan Vinh

For: NITRIDE OFFSET SPACER TO MINIMIZE SILICON RECESS BY USING
POLY REOXIDATION LAYER AS ETCH STOP LAYER

LETTER SUBMITTING FORMAL DRAWINGS

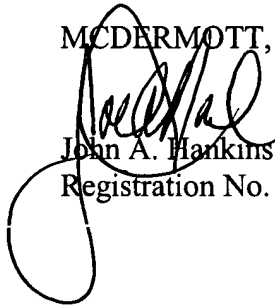
Mail Stop.Issue Fee
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

It is respectfully requested that the (4) four sheets of formal drawings submitted
herewith replace the sheets of informal drawings currently on file in connection with the
captioned application.

Respectfully submitted,

MCDERMOTT, WILL & EMERY


John A. Harkins
Registration No. 32,029

600 13th Street, N.W.
Washington, DC 20005-3096
(202) 756-8000 JAH:blp
Facsimile: (202) 756-8087
Date July 9, 2004